

(19)
(12)(KR)
(A)(51) 。 Int. Cl. ⁷
G02F 1/136(11)
(43)2001 - 0106849
2001 12 07(21) 10 - 2000 - 0027832
(22) 2000 05 23

(71)

3 416

(72)

4 5 201

(74)

()

:

(54)

가

가

가

,

.

,

,

.

,

,

.

가

,

.

1

,

,

,

,

1			,
2	1	II - II'	,
3		2	,
4		3	PVA ,
5a	5d	4	, , ,
6		4	PVA (patterned vertical align)
7a	7d	6	, , .

가

가

가

가

(black matrix)

(black matrix)

가

가

가

[illegible]

(10) 가 (90) (100) 0.5 - 3.0 μm (100) 3.0 - 4.0 가
 (SiO_x) (22, 26) (62, 65, 66)
 (90)

(50) (Al) (Al alloy), (Mo) - (MoW)
 (Cr), (Ta), (Cu) (Cu alloy)
 가 (22) (22)
 (26) (22) (82)
 (82) (22)
 가 (22, 26)
 (90) 가 (92) (94)
 (28)

(100) (SiN_x) (30) (22, 26)
 (26) (30) (hydrogenated amorphous silicon)
 (40) (40) (P) n
 (ohmic contact layer) (55, 56) (26)

(30) (55, 56) 가
 (62), (62) (55)
 (65) (62, 65) (26) (65)
 (56) (66)

(62, 65, 66) (70) , (70) (66)
 (76) 가 (70)

(70) (82) ITO(indium tin oxide) IZO(indium zinc oxide) (82)
 (72) (66)
 (82) (90)가 (b) 0.5 - 2 μm 가 (82) (
 62) (c) 2 - 6 μm 가 (82) (
 a) (62) b c 가 (62)

, 2 (10) (200)
 (210)가 (220) (220)
 (220) (82)
 (230) (90) (210)

(200) (22, 26) (62, 65, 66)
(210) 4 μm (210) 가 .

(10) $\frac{1}{(90)}$ 가 $(10, 200)$ (82) 가

1 (22) (62) 가 .

3 2 .

$$\begin{array}{ccccccc} 3 & & 2 & & (90) & & \\ (96)가 & , & (96)가 & , & (90) & , & (96) \\ 26, 1 &) & (62, 65, 66, 1 &) & (96)가 & & (96) \\ & & & & (22, 26) & & (62, 65, 66) \\ & & & & (22, 26) & & (62, 65, 66) \end{array} \quad (22,$$

1 (82) 가

,

가 (cross - talk)

.

,

(94)가 (62) (62) (62) (62)

$$\begin{aligned} & \quad 1 \quad 2 \quad (90) \text{가} \quad (92) \text{가} \\ & \quad (94) \text{가} \quad , \quad \text{가} \quad (92) \quad (94) \\ & \quad \cdot \quad , \quad (90) \text{가} \quad (92) \quad (94) \end{aligned}$$

4) , A (90) A B
 1 , (62) A
 (90) (94) (62) (62)
 , A (62) B (90) (9
 A (62) C (92) C
 D (22) 가 (92) (22)
 (22) , C (22) D
 (90) 가 (92) C (22) ,

(22) (62) (90) 가 (92) (

 94)

 , 가 가

 가 (82) (230) [PVA(patterned ve

 rtically aligned)] (fringe field)

 (pretilt) 4

 PVA (82, 230)

 PVA (90) (1

 0) 가 ,

 .

 4 3 PVA ,

 5a 5d 4 ,

 4 5a 5d , 1

 4 5a , 가 (90) 가 (92) (94)

 . 1 , (90) 가 (92)가

 4 5b , 가 (22) (22)

 (26) , (82)

 (25) , (25) (251) 가

 (22, 26, 25, 251) (90) (94)

 1 (28) (90) (94)

 .

 4 5c , (22)

 (62), (62) (26) (65)

 (26) (65) (66) , (62, 65, 66)

 (25) , (82) (25)

 (64) (62, 65, 66, 64)

 (90) 가 (92) 2 (68)

 (90) 가 (92) 76 74 (66)

 (64) (70, 2) (76, 74)

 (66) (64) (82)

 .

 4 5d , (82) (82) 가 가 1

 (81)가 , 1 (81) (82) 가

 가 2 (83)가 , 1 (81) (82) 가

 가 3 (85)가 , 232 234 2 (8

3) (230, 2) 4 5 ,
 231 233 3 (85) (230, 2)
) 6 7 .

PVA , (90) 가 (92) (94)가 ,
 , (90) 10% .

4 , , .

6 4 PVA ,
 7a 7d 6 , ,
 6 7a 7d 4 .

6 7a 7d , 3 .

4 가 ,
 , 6 7a 7d , (90)
 가 (25)
 (22, 26) (25) , (25)
 (82) 가 1 4 (86, 87, 8

8, 89) 가 1
 (texture) 가 4 (86, 87, 88, 89) 가 1
 (252) . 1 4 (86, 87, 88, 89)
 4 (86, 87, 88, 89) 2
 (253) , 7d 231, 232, 233 234 3
 가 (230) .

(57)

1.

가

,가

,

,

,

,

,

,

.

2.

1 ,

,

.

3.

2 ,

1

1

,

2

.

4.

3 ,

.

5.

1 ,

.

6.

5 ,

0.5 - 2 μm

.

7.

1 ,

2 - 6 μm

8.

1 ,

9.

1 ,

0.5 - 3 μm

10.

1 ,

가

11.

1 ,

가

,

,

12.

1 ,

13.

1

, 가

2

,

,

가

1

2

,

1

2

14.

1 ,

1 , 가

,

,

?d1020010106848 ? , 가

,

,

,

,

,

,

,

1 2 ,

1 2 ,

.

15.

14 ,

,

.

16.

15 ,

1 1 ,

2 .

17.

14 ,

1 2 .

18.

14 ,

가 .

19.

14 ,

가 .

20.

18 19 ,

4

21.

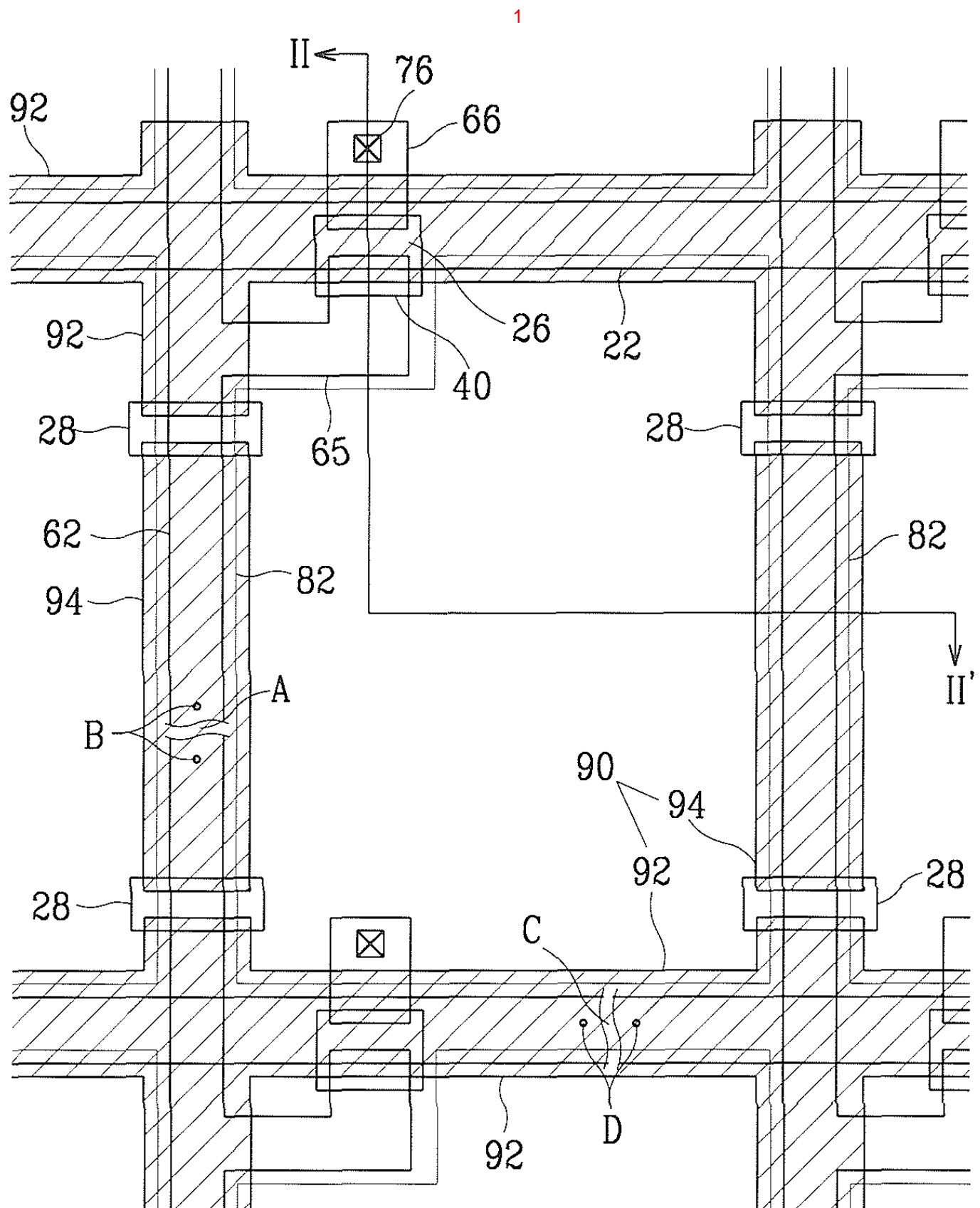
20 ,

22.

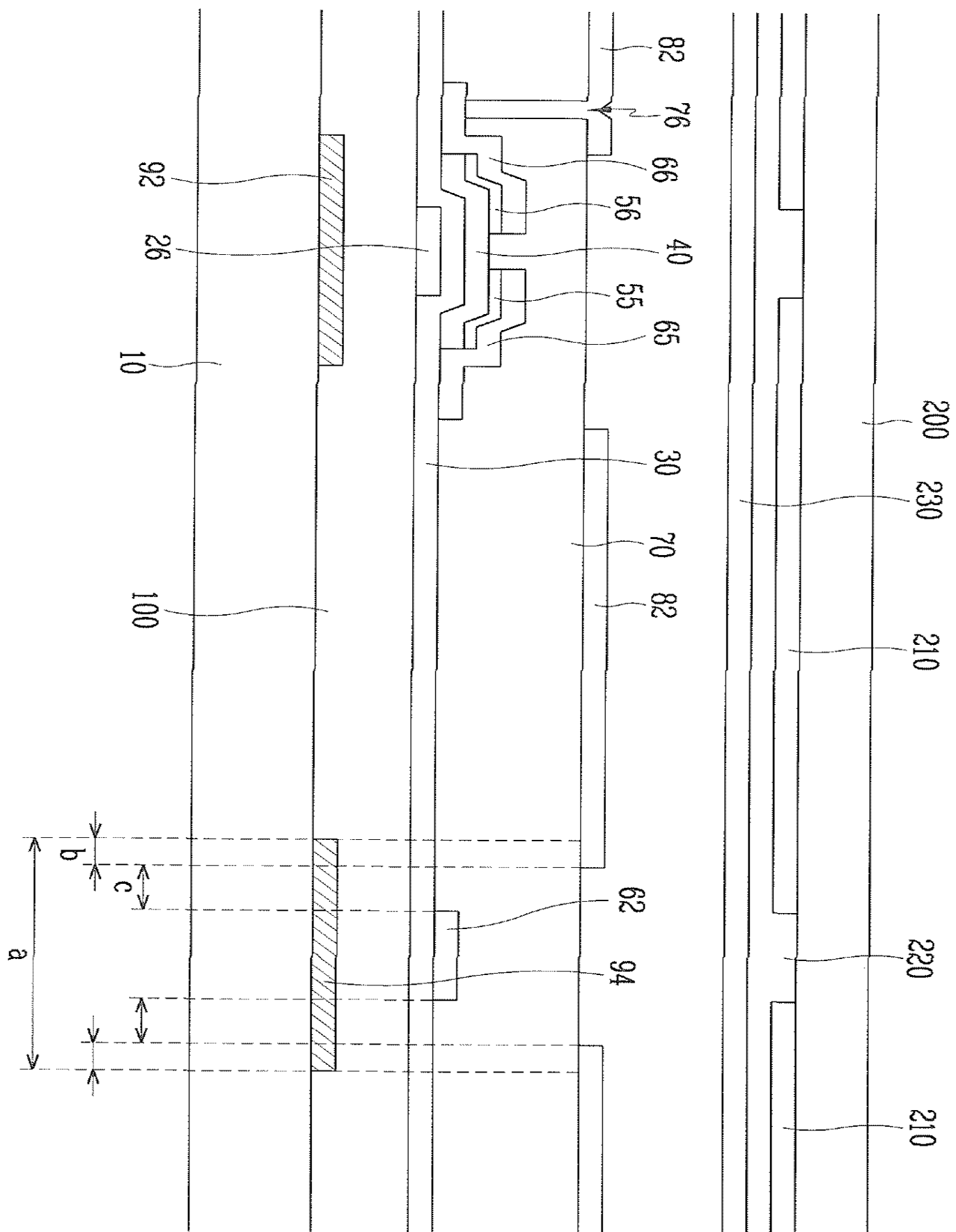
21 ,

가

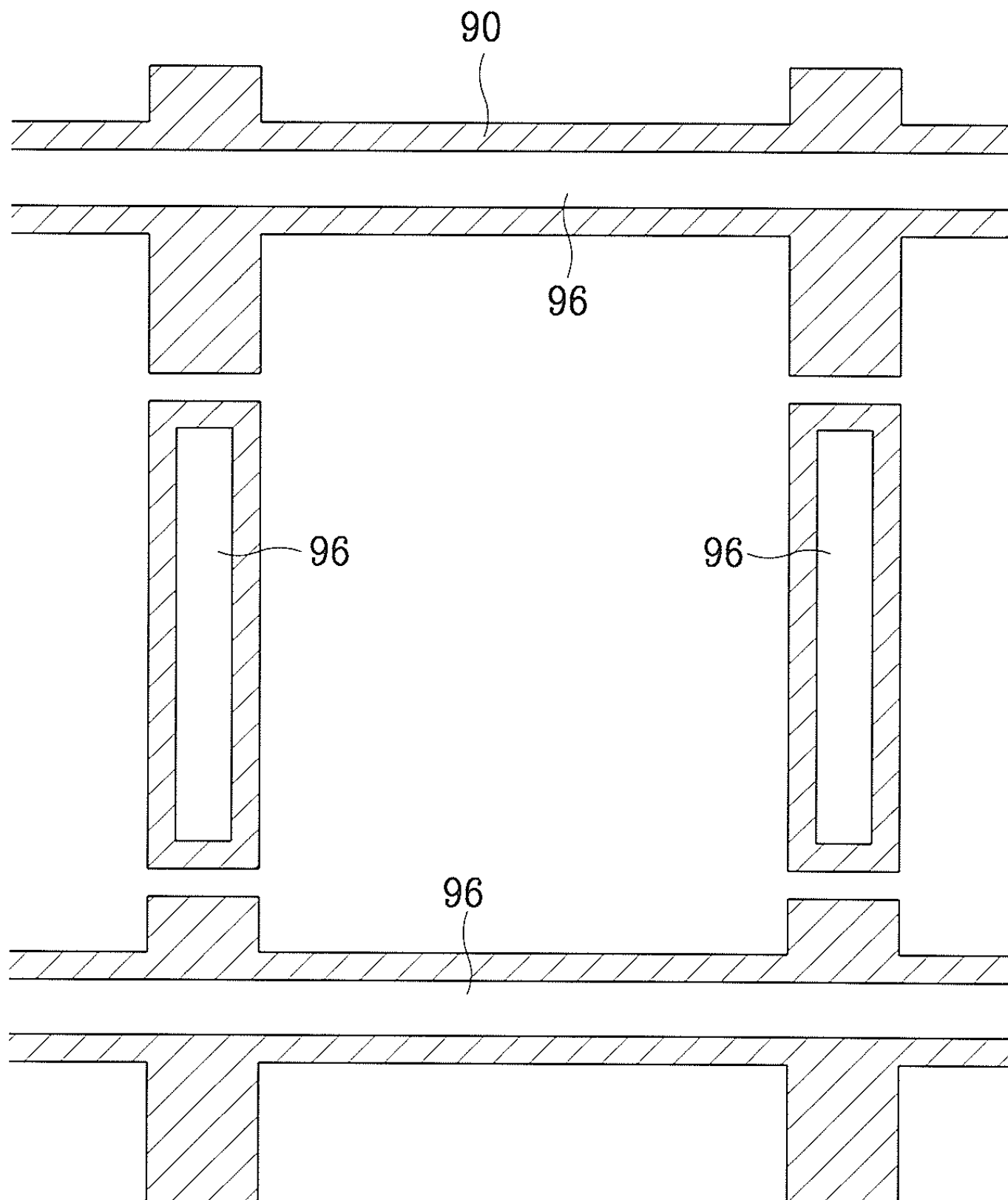
.



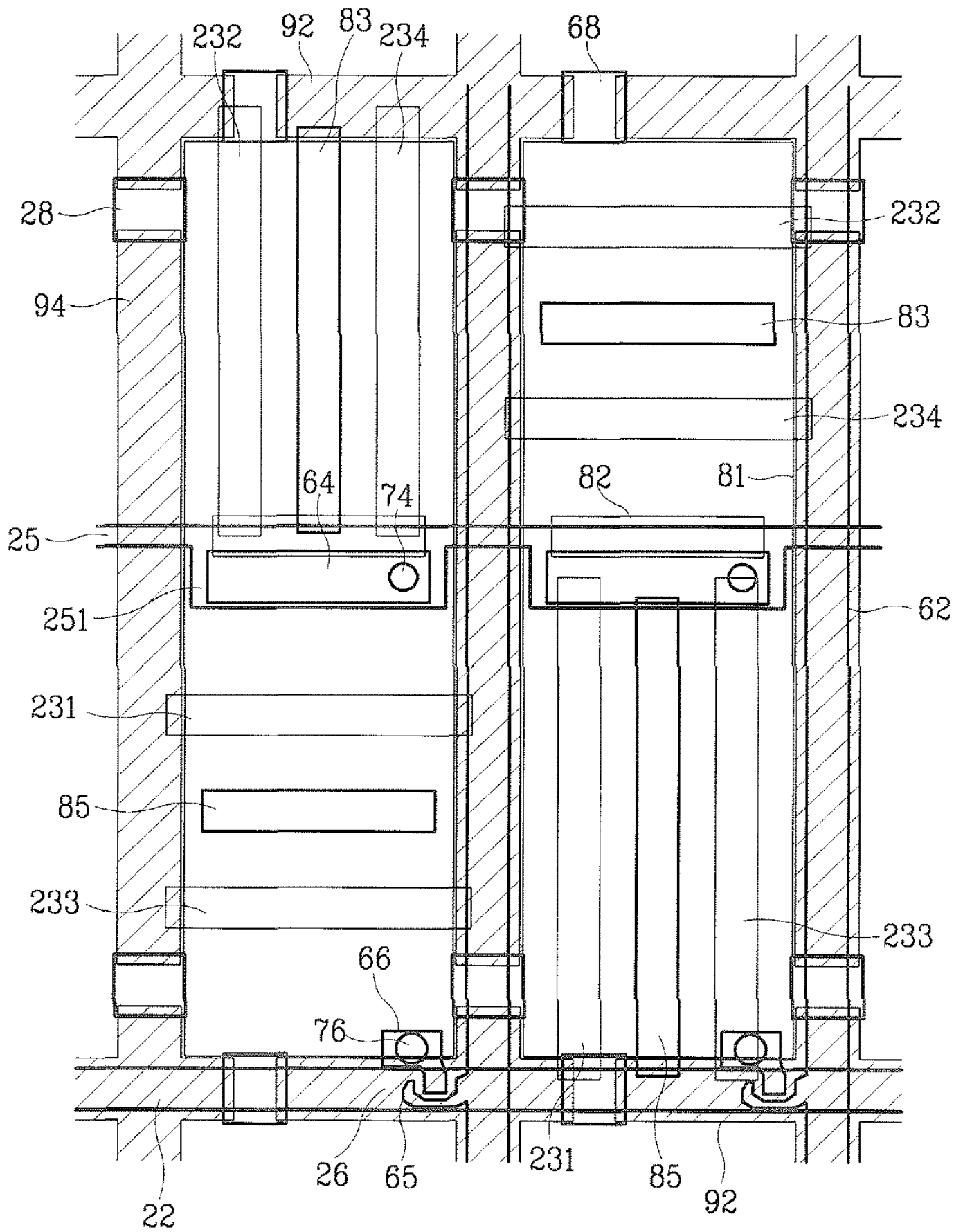
2



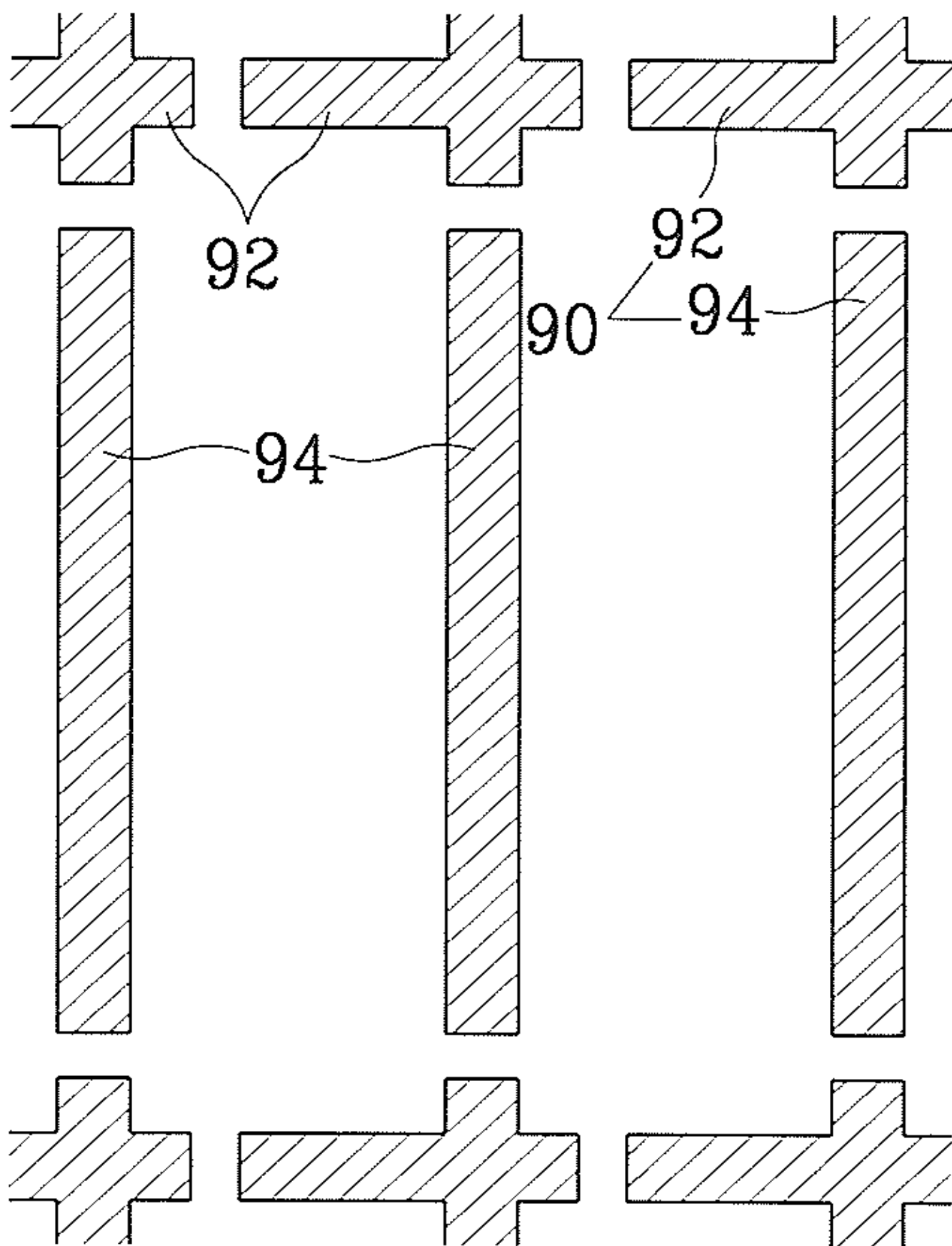
3



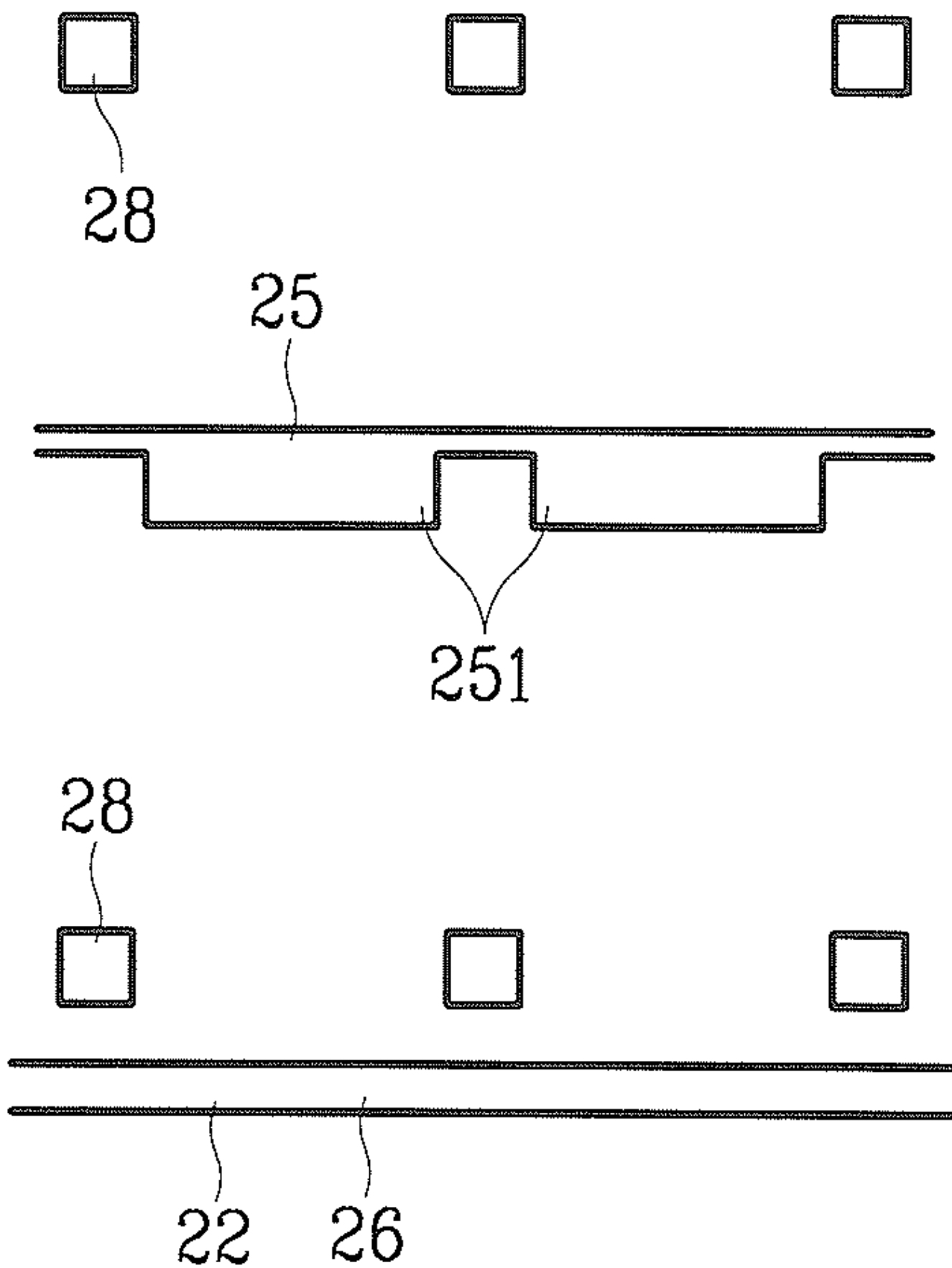
4



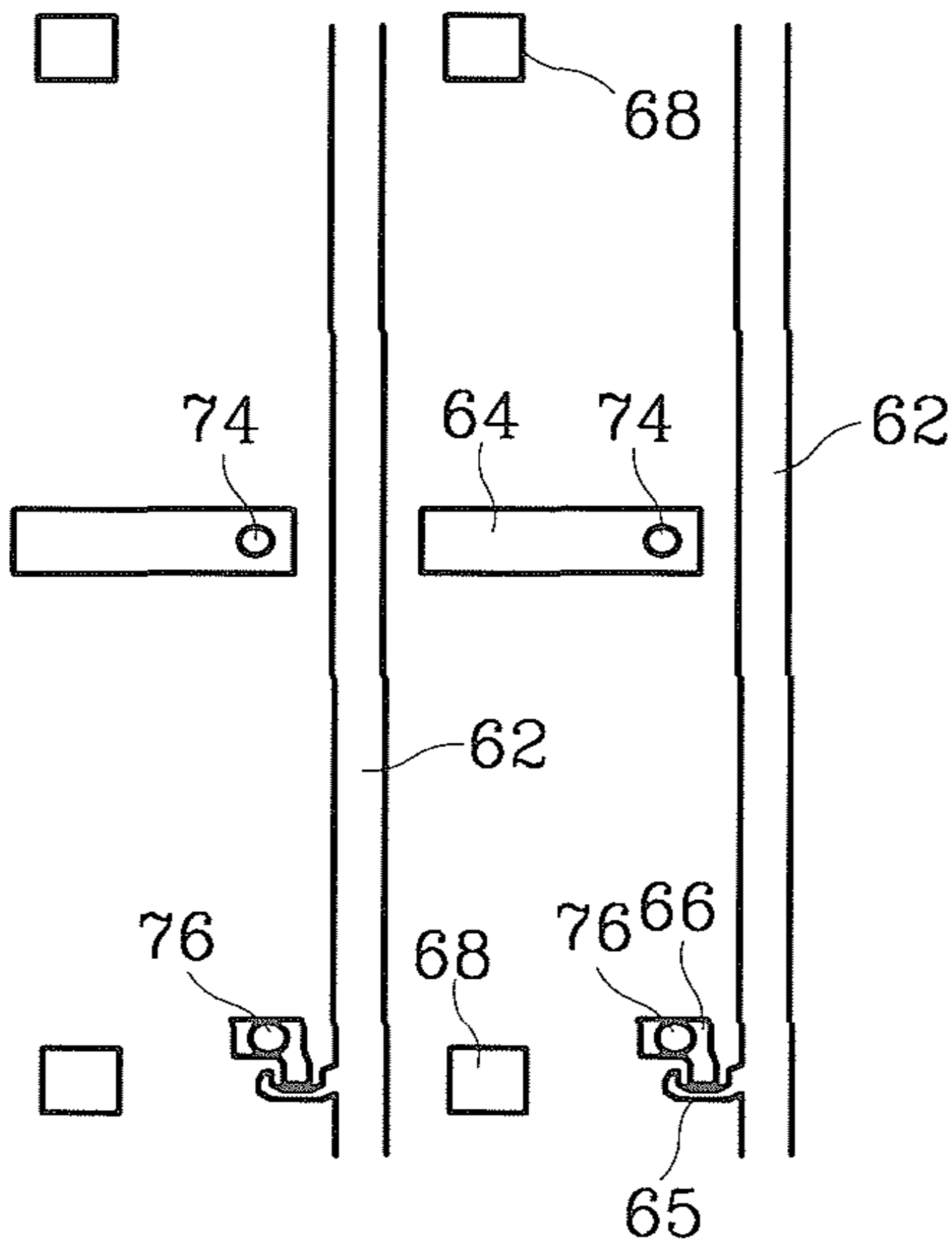
5a



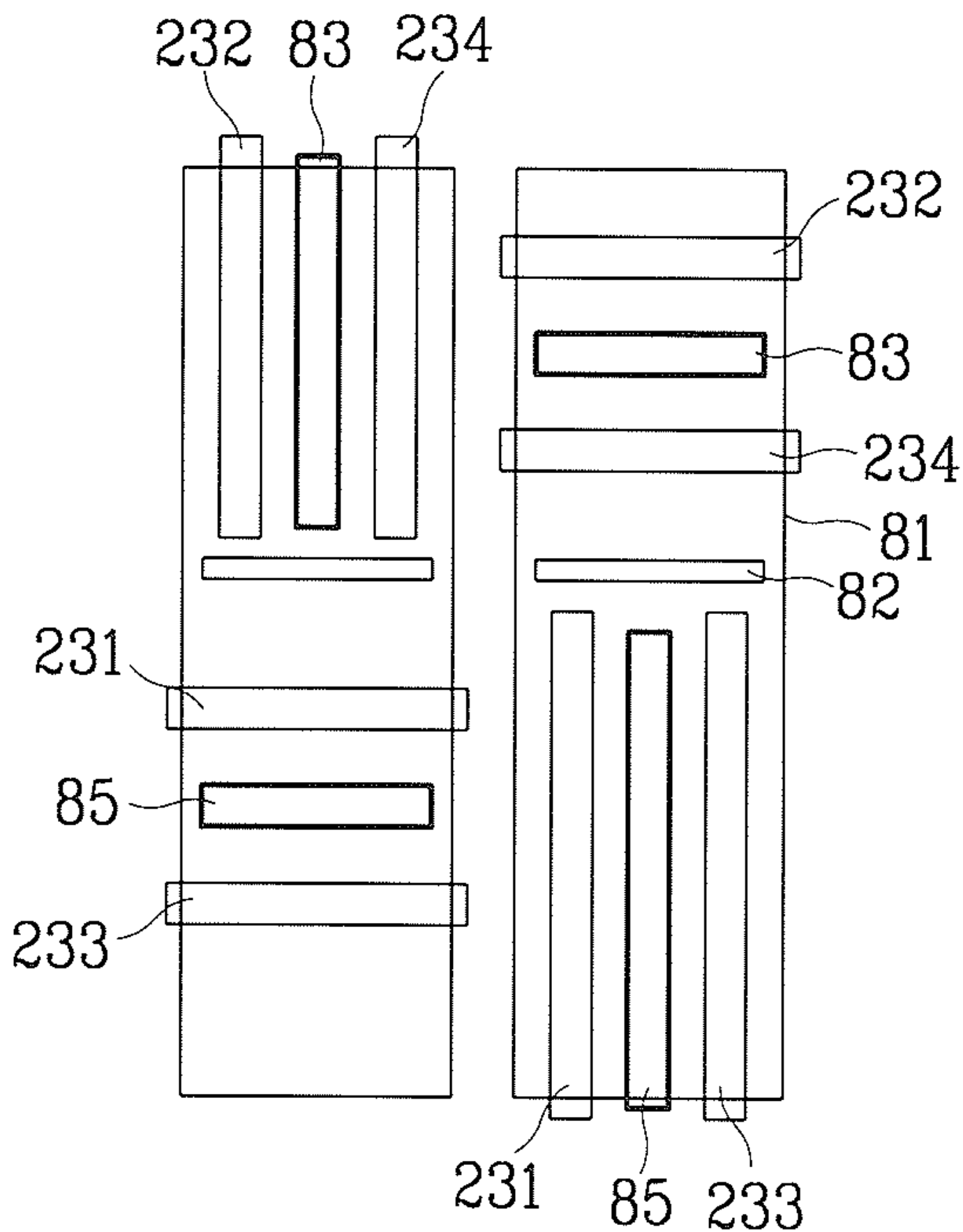
5b



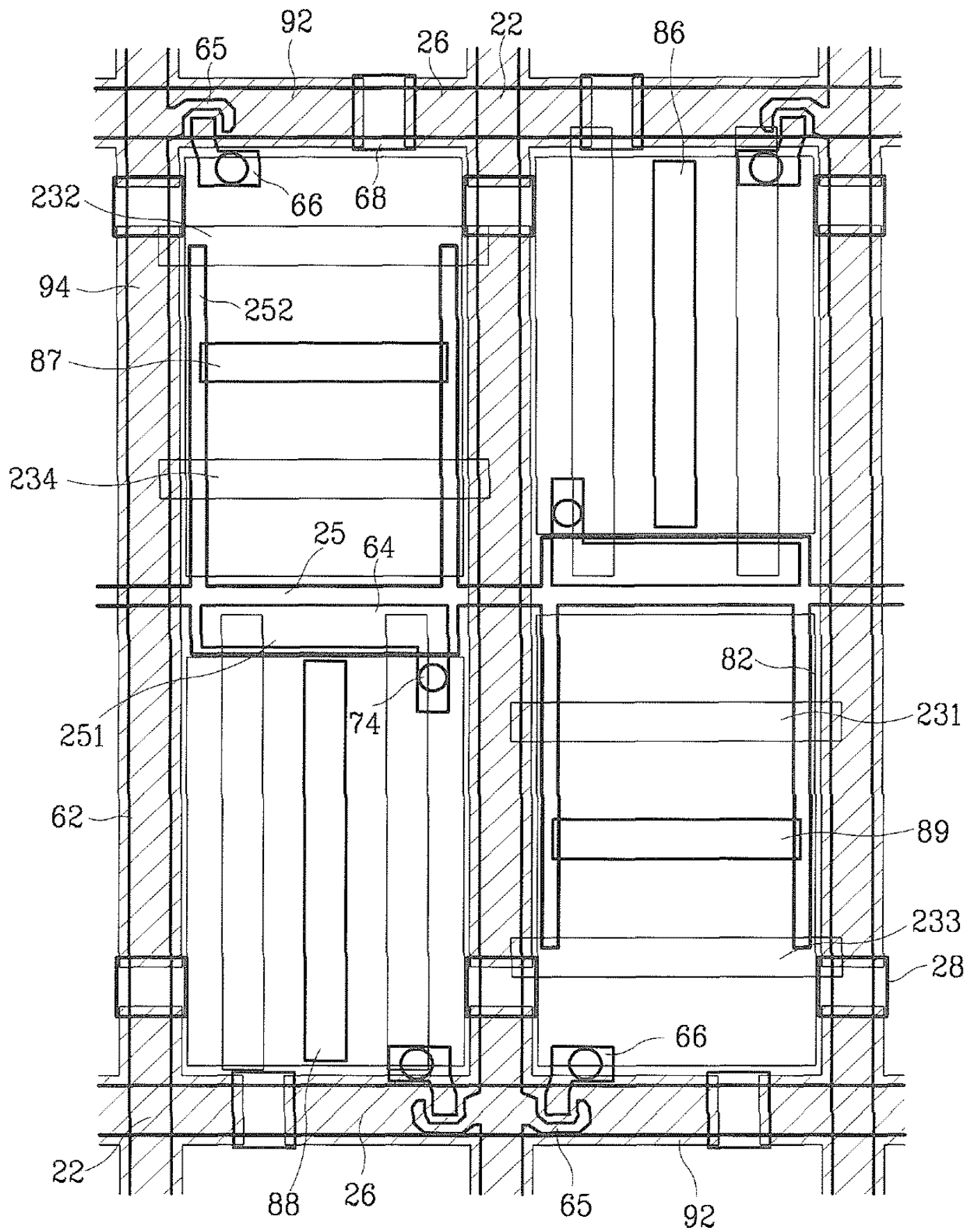
5c



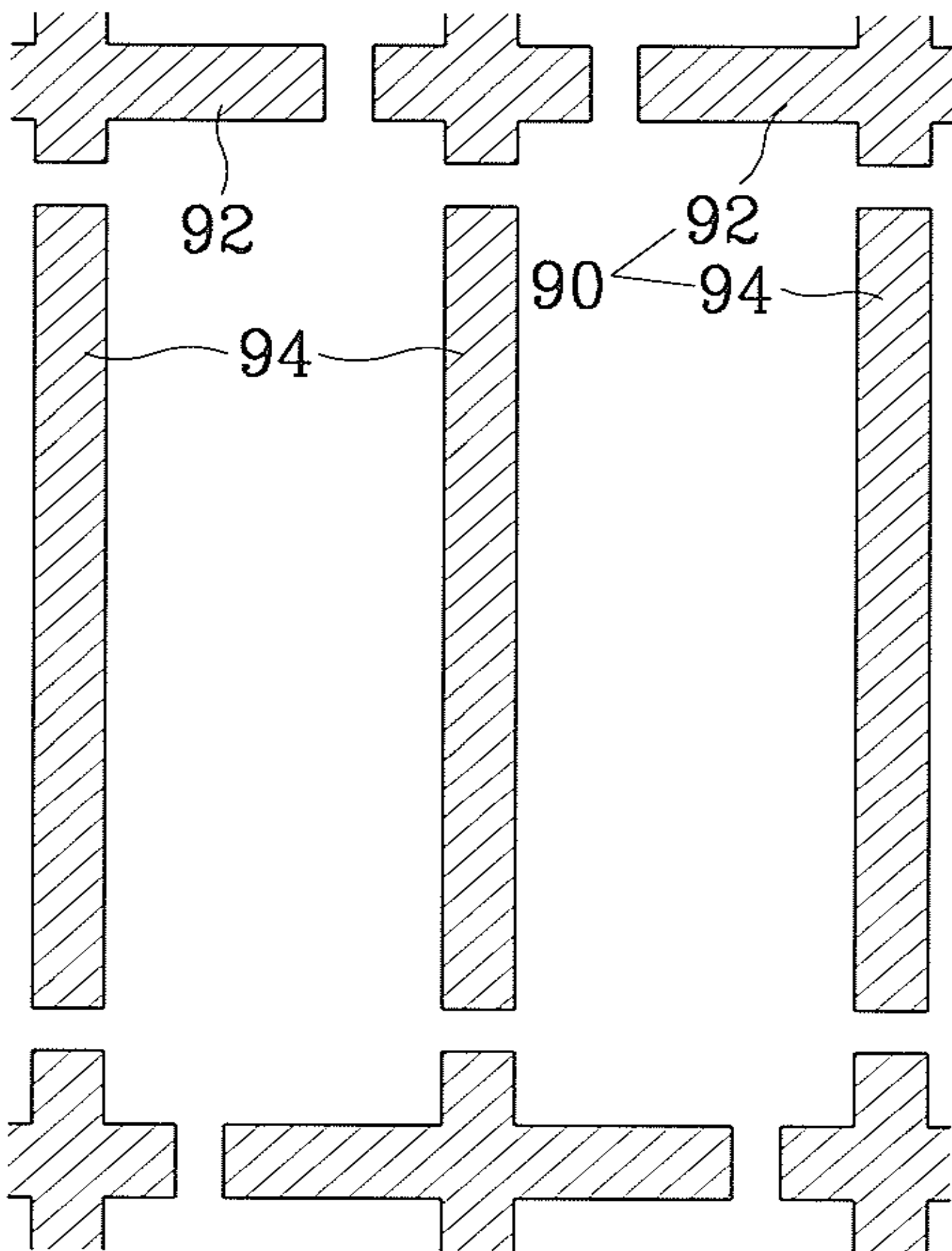
5d



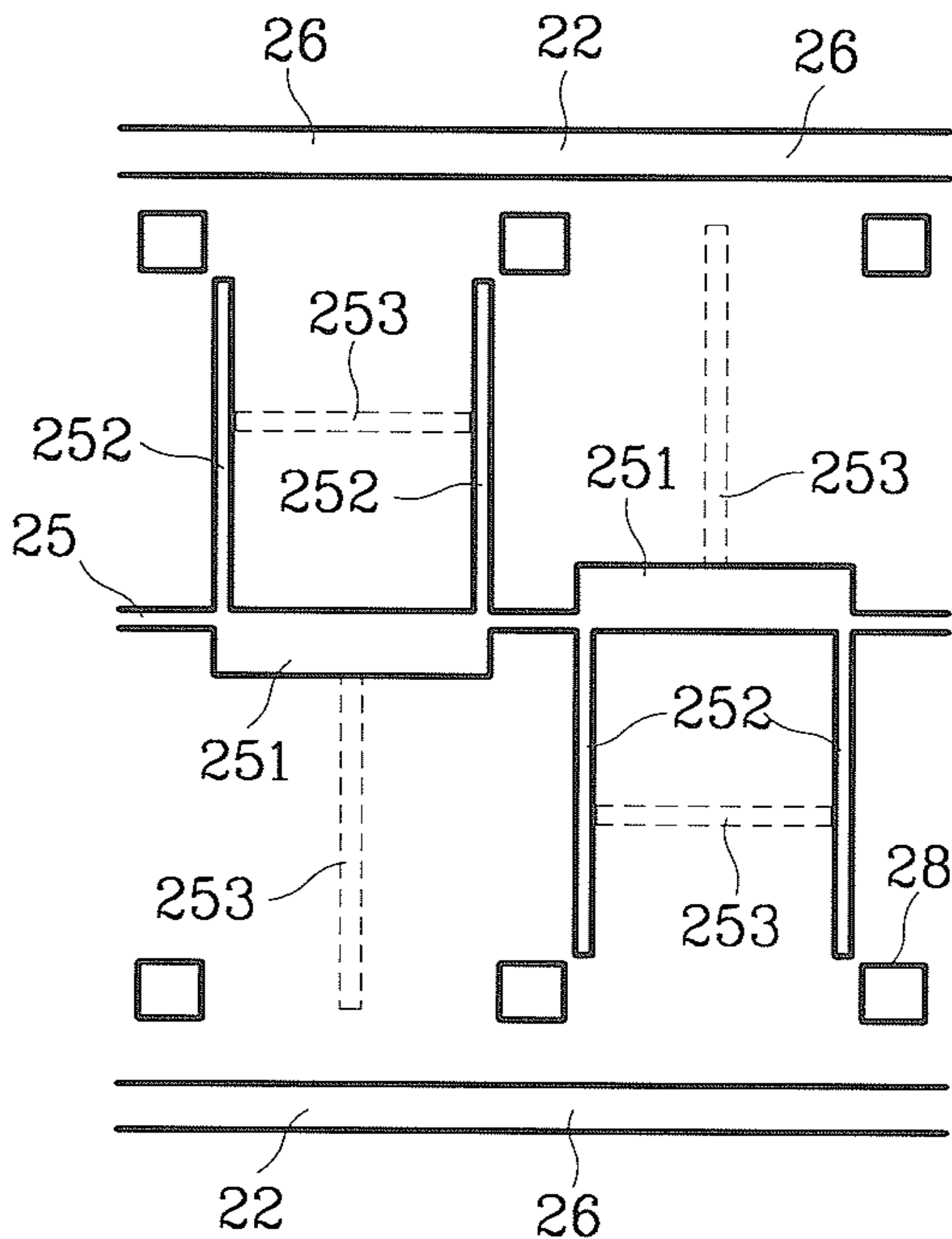
6



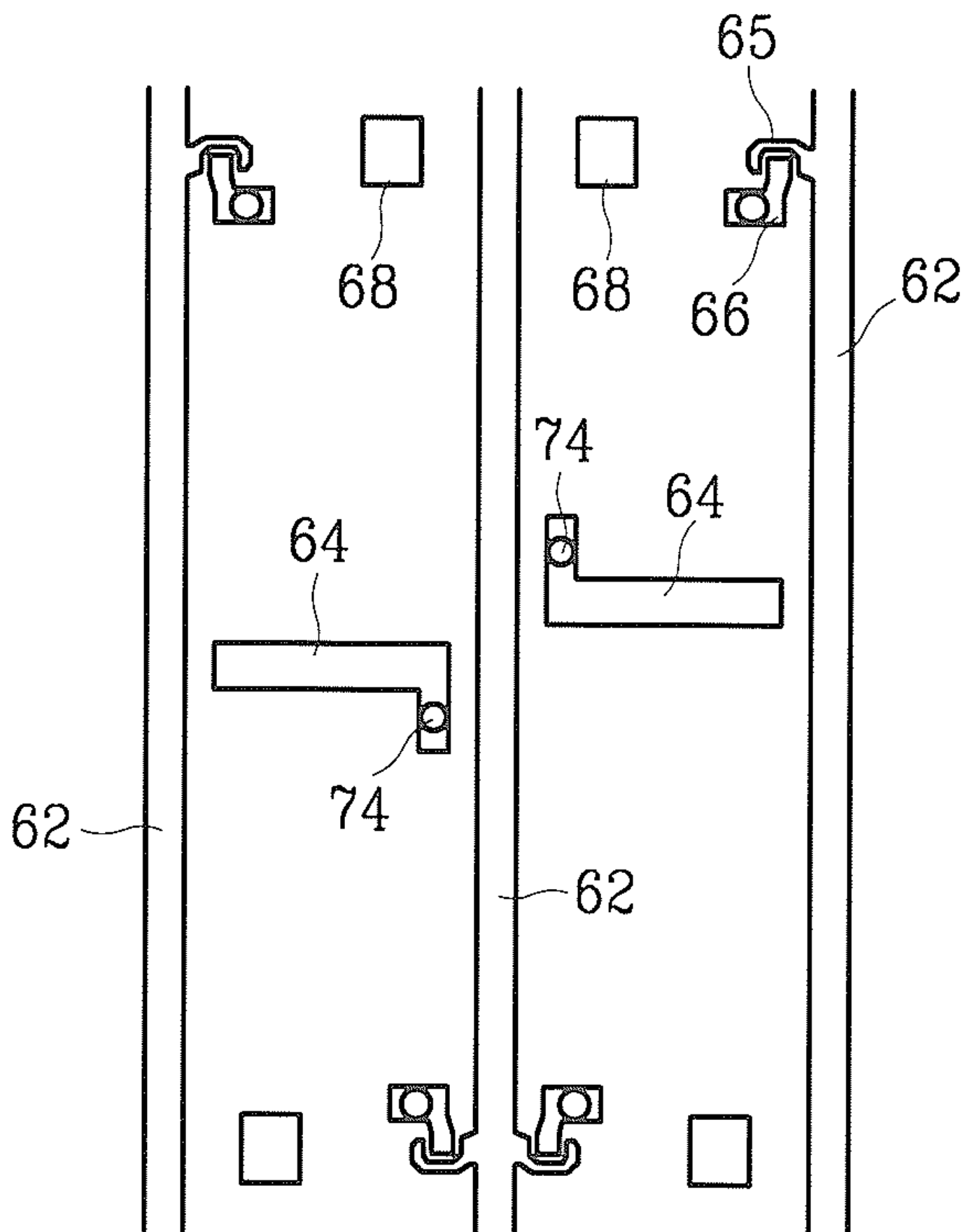
7a



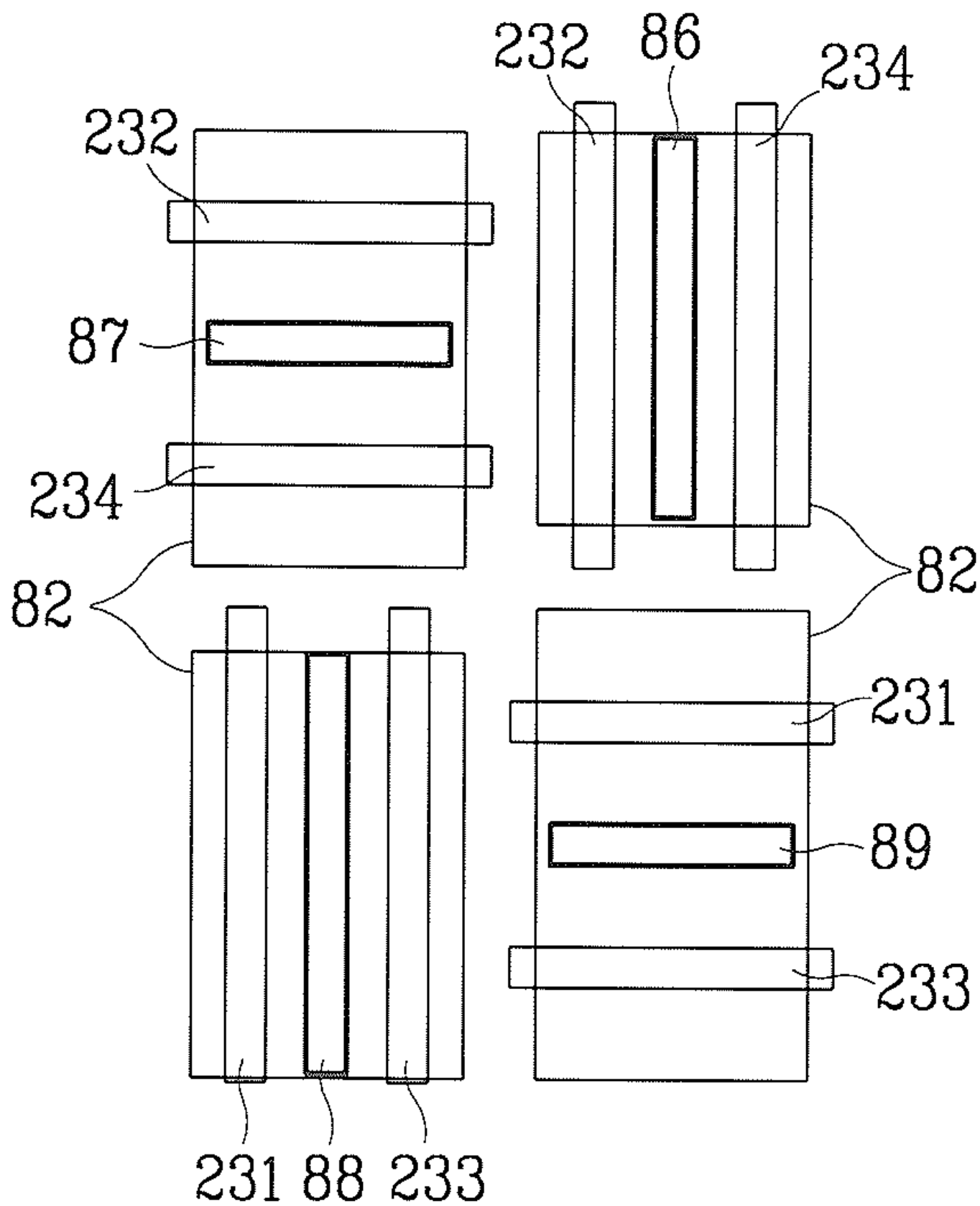
7b



7c



7d



专利名称(译)	用于液晶显示器的薄膜晶体管基板及其修复方法		
公开(公告)号	KR1020010106849A	公开(公告)日	2001-12-07
申请号	KR1020000027832	申请日	2000-05-23
[标]申请(专利权)人(译)	三星电子株式会社		
申请(专利权)人(译)	三星电子有限公司		
当前申请(专利权)人(译)	三星电子有限公司		
[标]发明人	SONG JANGKUN 송장근		
发明人	송장근		
IPC分类号	G02F1/1368 G02F1/1343 G02F1/1362 G02F1/1335 G02F1/13 G02F1/136		
CPC分类号	G02F1/136259 G02F1/134363 G02F1/1309 G02F1/136209 G02F2001/136263		
代理人(译)	您是我的专利和法律公司 KIM , WON GUN		
其他公开文献	KR100623989B1		
外部链接	Espacenet		

摘要(译)

在绝缘基板上，通过彼此分开的水平部分和垂直部分形成在像素中具有开口的网状黑矩阵，并形成覆盖黑矩阵的绝缘膜。在绝缘膜上形成包括栅极线和连接到栅极线的栅极的栅极线，并形成覆盖栅极线的栅极绝缘膜。在栅极绝缘层上依次形成半导体层和欧姆接触层，与栅极线交叉并限定像素的数据线，连接到数据线的源极和连接到源极的源极，并且形成包括漏电极的数据线。数据线覆盖有保护膜，该保护膜具有用于暴露漏电极的接触孔，并且在保护膜上形成通过接触孔连接到漏电极的像素电极。 1 指数方面 孔径比，黑色矩阵，单线，水平对齐，垂直对齐

